

Review of Polymer Solutions for Near-Field Electrospinning with Spatial Control

Antonio Osamu Katagiri Tanaka, Héctor Alán Aguirre Soto

Abstract

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Contents

1	Introduction	1
2	NFES	2
3	Polymer Solution and Process Parameters	12
4	Applications	12
5	Fiber Characterization	12
6	Conclusion	12
	References	12

1. Introduction

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2. NFES

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Table 1: Electrospun Polymer Solutions - Solution and Process Parameters

Polymer(s)	Solvent(s)	NFES Variant	Process Parameters and Fiber Characterization	Ref.
Poly(ethylene oxide) (PEO)	Deionized water	Low-Voltage NFES	Solution Concentration: 1, 2, and 3 <i>wt%</i> PEO Nozzle: 27 gauge type 304; stainless steel needle Solution deposition rate: lower than $1\mu L/h$ Nozzle-to-substrate distance: $1mm$ Substrate composition: Pyrolyzed SU-8 carbon and Si Applied voltage: polymer jet initiated at 400-600 <i>V</i> and dispensed at 200-400 <i>V</i> x-y stage velocity: $10\text{-}40mm/s$ Fiber Diameter: $50\text{-}425nm$ Distance between adjacent fibers: <i>Not determined</i>	[1]
Poly[2-methoxy-5-(2-ethylhexyloxy)-1,4-phenylenevinylene] (MEH-PPV) with Poly(ethylene oxide) (PEO)	acetonitrile toluene mixture (65/35); acetic acid toluene (17/83); pure toluene	Typical process	NFES Solution Concentration: $10mg$ of MEH-PPV in $2mL$ of toluene; $500mL$ of MEH-PPV solution with $250mg$ of PEO in $3.5mL$ of acetonitrile; $500mL$ of MEH-PPV solution with $250mg$ of PEO in $3mL$ of acetic acid / toluene (17 / 83). The resulting MEH-PPV/PEO concentration is 1:100 Nozzle: mm-diameter tip Tungsten spinneret in a 26 gauge needle Solution deposition rate: $50\mu L/h$ Nozzle-to-substrate distance: $500\mu m$ Substrate composition: SiO ₂ /Si (oxide thickness = 800 nm) Applied voltage: around $1.3kV$ x-y stage velocity: $50cm/s$ Fiber Diameter: $100nm$ Distance between adjacent fibers: around $100\mu m$	[2]

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<i>Table 1 continued</i>				
	Poly(ethylene oxide) (PEO)	Water	Scanning Tip Electrospinning and NFES	<p>Solution Concentration: 7wt% PEO [3]</p> <p>Nozzle: Needle outer diameter of 200μm and inner diameter of 100μm</p> <p>Solution deposition rate: 0.1$\mu L/h$</p> <p>Nozzle-to-substrate distance: 500μm</p> <p>Substrate composition: <i>Not determined</i></p> <p>Applied voltage: polymer jet initiated at 1.5 kV and dispensed at 600V</p> <p>x-y stage velocity: 120mm/s</p> <p>Fiber Diameter: 709\pm131nm; 49-74nm when applied voltage is 800V</p> <p>Distance between adjacent fibers: <i>Not determined</i></p> <p>Notes: 108m yield in 15min with a fiber diameter of 709\pm131nm</p>
4	Poly(vinylidene fluorid) (PVDF)	N,N Dimethyl-formamide (DMF)	Helix Electrohydro-dynamic Printing (HE-printing)	<p>Solution Concentration: 1.8g PVDF in 4.1g of DMF and 4.1g of acetone. The resulting concentration is 18% PVDF. [4]</p> <p>Nozzle: Needle outer diameter of 510μm and inner diameter of 260μm</p> <p>Solution deposition rate: 400nL/min</p> <p>Nozzle-to-substrate distance: 10-50mm</p> <p>Substrate composition: Poly(dimethylsiloxane) (PDMS) on Ecoflex</p> <p>Applied voltage: 1.5–3kV</p> <p>x-y stage velocity: 0-400mm/min</p> <p>Fiber Diameter: about 1.5-3μm</p> <p>Distance between adjacent fibers: <i>Not determined</i></p>

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<i>Table 1 continued</i>				
Polyhedral Oligomeric Silsesquioxane- Poly(Carbonate- Urea)Urethane (POSS-PCU) and Polyhe- dral Oligomeric Silsesquioxane Poly(Caprolactone- Poly(Carbonate- Urea)Urethane) (POSS-PCL- PCU)	Dimethyl acetamide (DMAC) and 1-Butanol	Electrohydro- dynamic 3D Print-patterning or Electrohydro- dynamic Jetting	Solution Concentration: POSS-PCU and POSS- PCL-PCU used in 20%w/w concentration in DMAC Nozzle: needle of 750 μm in diameter Solution deposition rate: less than 1 $\mu L/min$ Nozzle-to-substrate distance: about between 500 μm to 2mm Substrate composition: <i>Not determined</i> Applied voltage: 8.0-10.0kV x-y stage velocity: 10mm/s Fiber Diameter: 5-50 μm Distance between adjacent fibers: 250 μm	[5]
Poly(ethylene ox- ide) (PEO)	Distilled water	Electrohydro- dynamic Writing or Mechano- electrospinning (MES)	Solution Concentration: 6wt% PEO Nozzle: <i>Not determined</i> Solution deposition rate: 1200nL/min Nozzle-to-substrate distance: 7.5mm Substrate composition: <i>Not determined</i> Applied voltage: polymer jet initiated at 2 kV and dispensed at 0.8-1kV x-y stage velocity: around 400mm/s Fiber Diameter: 200-350nm Distance between adjacent fibers: 5 μm	[6]

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<i>Table 1 continued</i>				
Poly(ethylene oxide) (PEO)	Deionized water and the ethanol with a volume ratio of 3:1	Airflow-assisted Electrohydrodynamic Direct-writing (EDW)	Solution Concentration: 8wt% PEO Nozzle: Outer airflow passage diameter: 1mm Airflow gas pump pressure: 25kPa Inner liquid passage diameter: 0.21mm Solution deposition rate: 30 μ L/h Nozzle-to-substrate distance: 2mm Substrate composition: Silicon Applied voltage: about 2kV x-y stage velocity: 1-20mm/s Fiber Diameter: 3.73 \pm 1.37 μ m Distance between adjacent fibers: 5.13 \pm 6.67 μ m	[7]
Poly(Vinylidene Fluoride) (PVDF)	Acetone and Dimethyl Sulfoxide (DMSO)	3D Electrospinning	Solution Concentration: 17wt% PVDF; 1.7g of PVDF, 5g of acetone, 0.5g of Capstone FS-66, 5g of DMSO Nozzle: Needle inner diameter of 100 μ m Solution deposition rate: 14 nL/min Nozzle-to-substrate distance: 750 μ m Substrate composition: A4 size commercial printing paper (Double A) Applied voltage: 1.9kV x-y stage velocity: 10mm/s Fiber Diameter: Not determined Distance between adjacent fibers: Not determined	[8]

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<i>Table 1 continued</i>				
Poly(9-Vinyl Carbazole) (PVK)	Styrene	Typical process	NFES	Solution Concentration: 3.96wt% PVK in styrene [9] Nozzle: Needle inner diameter of 100 μm Solution deposition rate: 500nL/min Nozzle-to-substrate distance: around 2.5mm Substrate composition: Si/SiO ₂ Applied voltage: 3-4kV x-y stage velocity: 13.3cm/s Fiber Diameter: 289.26 \pm 35.37nm Distance between adjacent fibers: 50 μm Notes: 15m yield in 2min
Polystyrene (PS)	1,2,4-Trichloro benzene	Electrohydrodynamic (EHD) jet printing		Solution Concentration: 1 to 5wt% PS [10] Nozzle: Glass nozzle inner diameter of 2 μm and outer diameter of 2.66 μm Solution deposition rate: Si Nozzle-to-substrate distance: 20, 30, 40 μm Substrate composition: Applied voltage: 500 to 400V in 25V increments x-y stage velocity: 0.01-10mm/s Fiber Diameter: about 60-170 μm Distance between adjacent fibers: <i>Not determined</i>
Poly(ethylene oxide) (PEO)	<i>Not determined</i>	Typical process	NFES	Solution Concentration: 3wt% PEO [11] Nozzle: <i>Not determined</i> Solution deposition rate: <i>Not determined</i> Nozzle-to-substrate distance: 500 μm Substrate composition: Si Applied voltage: 1000V x-y stage velocity: 20cm/s Fiber Diameter: 300nm Distance between adjacent fibers: 25 μm

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<i>Table 1 continued</i>			
Poly(ethylene oxide) (PEO)	Distilled water	Multinozzle NFES	Solution Concentration: 5wt% [12] Nozzle: four-nozzle and six-nozzle array with needle spacing changes from 1.5mm to 3.5mm Solution deposition rate: 1-3 μ L/min Nozzle-to-substrate distance: 2mm Substrate composition: Not determined Applied voltage: 1.7-2.7kV x-y stage velocity: Not determined Fiber Diameter: 5.47 μ m Distance between adjacent fibers: 3-5 mm
Poly(ethylene oxide) (PEO)	Distilled water	Multinozzle NFES	Solution Concentration: 5wt% [13] Nozzle: Dual-28G-needle array with needle inner diameter of 0.18mm and outer diameter of 0.36mm; with needle spacing changes from 2.0mm to 3.0mm Solution deposition rate: 0.2 μ L/min Nozzle-to-substrate distance: 3.0-4.0mm Substrate composition: Not determined Applied voltage: 2.0-3.0kV x-y stage velocity: 20mm/s Fiber Diameter: Not determined Distance between adjacent fibers: 218-326 μ m

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Table 1 continued				
Poly(ethylene oxide) (PEO)	Distilled water	Multinozzle NFES	Solution Concentration: 5 wt% Nozzle: Dual-28G-needle array with needle inner diameter of 180 μm and outer diameter of 360 μm ; with needle spacing changes of 2.0mm Solution deposition rate: 0.2 $\mu L/min$ Nozzle-to-substrate distance: 4.0mm Substrate composition: chromium-plated glass Applied voltage: 2.5kV x-y stage velocity: 20mm/s Fiber Diameter: <i>Not determined</i> Distance between adjacent fibers: 2.3002-2.7224mm	
Poly(ethylene oxide) (PEO)	<i>Not determined</i>	Typical process	NFES	Solution Concentration: 2wt% Nozzle: G30 needle with inner diameter of 0.15mm Solution deposition rate: <i>Not determined</i> Nozzle-to-substrate distance: 1-3mm Substrate composition: Silicon Applied voltage: 1250V x-y stage velocity: <i>Not determined</i> Fiber Diameter: <i>Not determined</i> Distance between adjacent fibers: 20 μm

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<i>Table 1 continued</i>					
Gelatin (porcine skin)	Acetic and Acetate	Acid Ethyl	Typical process	NFES	<p>Solution Concentration: 11wt% gelatin, 30wt% wa- [16] ter, 35.4wt% acetic acid, 23.6wt% ethyl acetate</p> <p>Nozzle: 19G needle tip with outer diameter of 1.08mm</p> <p>Solution deposition rate: <i>Not determined</i></p> <p>Nozzle-to-substrate distance: 1.25mm</p> <p>Substrate composition: Poly(Dimethylsiloxane) (PDMS) films</p> <p>Applied voltage: 1000V</p> <p>x-y stage velocity: <i>Not determined</i></p> <p>Fiber Diameter: around 2-3μm</p> <p>Distance between adjacent fibers: 40μm</p>
Poly(ethylene ox- ide) (PEO)	Water/Ethanol (v/v = 60/40)		Typical process	NFES	<p>Solution Concentration: PEO concentrations of [17] 16% adn 18%</p> <p>Nozzle: 40μm</p> <p>Solution deposition rate:</p> <p>Nozzle-to-substrate distance: 1mm</p> <p>Substrate composition: Planar silicon</p> <p>Applied voltage: 1.7kV</p> <p>x-y stage velocity: 0.36m/s</p> <p>Fiber Diameter: 5.15μm</p> <p>Distance between adjacent fibers: <i>Not determined</i></p>

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<i>Table 1 continued</i>			
Poly(ethylene oxide) (PEO)	Water/Ethanol (v/v = 3/1)	Electrohydrodynamic Direct-Write (EDW)	Solution Concentration: 14wt% PEO [18] Nozzle: Stainless needle with inner diameter of 210 μm and outer diameter of 400 μm Solution deposition rate: 50 $\mu L/h$ Nozzle-to-substrate distance: 2mm Substrate composition: Poly(ethylene terephthalate) (PET) Applied voltage: 3kV x-y stage velocity: 700mm/s Fiber Diameter: 15-35 μm Distance between adjacent fibers: 70 μm

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Solution Concentration:

Nozzle:

Solution deposition rate:

Nozzle-to-substrate distance:

Substrate composition:

Applied voltage:

x-y stage velocity:

Fiber Diameter:

Distance between adjacent fibers:

3. Polymer Solution and Process Parameters

4. Applications

5. Fiber Characterization

6. Conclusion

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